

Amendments to the Claims

This listing of the Claims will replace all prior versions and listings of the claims in this patent application.

Listing of the Claims

1-15. (canceled)

16. (original) A silane abatement process comprising:

bubbling waste silane gas into a water-filled chamber;

reacting said waste silane gas with oxygen dissolved in water in said water-filled chamber whereby SiO_2 precipitates are formed and wherein said SiO_2 precipitates settle to a bottom surface of said water-filled chamber; and

draining said SiO_2 precipitates out of said water-filled chamber.

17. (original) The process according to Claim 16 further comprising flowing N_2 gas at high pressure to push said waste silane gas into said water-filled chamber.

18-25. (canceled)

26. (new) The process according to Claim 16 wherein said reacting of said waste silane gas with said oxygen occurs under said water in said water-filled chamber.

27. (new) A silane abatement process comprising:

bubbling waste silane gas into a water-filled chamber wherein said waste silane gas enters said chamber under the water;

reacting said waste silane gas with oxygen dissolved in said water in said water-filled chamber whereby SiO_2 precipitates are formed and wherein said SiO_2 precipitates settle to a bottom surface of said water-filled chamber; and

draining said SiO_2 precipitates out of said water-filled chamber.

28. (new) The process according to Claim 27 further comprising flowing N_2 gas at high pressure to push said waste silane gas into said water-filled chamber.

29. (new) The process according to Claim 28 wherein said high pressure is about 100 psi.

30. (new) A silane abatement process comprising:

providing waste silane gas from a manufacturing process;

without first applying a combustion process, bubbling waste silane gas into a water-filled chamber wherein said waste silane gas enters said chamber under the water;

reacting said waste silane gas with oxygen dissolved in said water in said water-filled chamber whereby SiO_2 precipitates are formed and wherein said SiO_2 precipitates settle to a bottom surface of said water-filled chamber; and

draining said SiO_2 precipitates out of said water-filled chamber.

31. (new) The process according to Claim 30 further comprising flowing N₂ gas at high pressure to push said waste silane gas into said water-filled chamber.

32. (new) The process according to Claim 31 wherein said high pressure is about 100 psi.

33. (new) The process according to Claim 30 further comprising supplying a continuous fresh air intake into said water-filled chamber.